

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A cleaning apparatus to clean alien substance from a substrate provided with a mask pattern, the apparatus comprising:

an ultraviolet cleaner for cleaning the alien substance remaining on the substrate after developing the mask pattern; and

a conveyer for in-line conveying the substrate to and from the ultraviolet cleaner for wet etching;

wherein the ultraviolet cleaner is installed at a predetermined area in a loader on which a plurality of cassettes arranged with the substrate are loaded.

2. (Currently Amended) The apparatus according to claim 1, wherein the conveyer includes:

a first conveyer conveying the substrate from a the loader to the ultraviolet cleaner; and

a second conveyer conveying the substrate from the ultraviolet cleaner to a wet etching unit.

3. (Original) The apparatus according to claim 1, wherein the ultraviolet cleaner uses eximer ultraviolet light.

4. (Original) The apparatus according to claim 1, wherein the substrate includes at least one of a gate electrode, a source electrode, a drain electrode, a pixel electrode, and a protective layer.

5. (Original) The apparatus according to claim 1, wherein the substrate includes at least one of a black matrix and a common electrode.

6. (Currently Amended) A wet etching apparatus to clean alien substances from a substrate with a mask pattern prior to wet etching, the apparatus comprising:

an ultraviolet cleaner for cleaning the alien substances from the substrate after developing the mask pattern;

a conveyer conveying the substrate to and from the ultraviolet cleaner;

a loader loading the substrate to and from the ultraviolet cleaner, the ultraviolet cleaner being installed at a predetermined area in the loader on which a plurality of cassettes arranged with the substrate are loaded; and

an etching unit etching the substrate that is free of the alien substances, the conveyer conveying the substrate from the ultraviolet cleaner into the etching unit.

7. (Original) The apparatus according to claim 6, wherein the conveyer includes:

a first conveyer conveying the substrate from the loader to the ultraviolet cleaner; and

a second conveyer conveying the substrate from the ultraviolet cleaner to the etching unit.

8. (Canceled)

9. (Original) The apparatus according to claim 6, wherein the conveyer is installed at a predetermined area between the ultraviolet cleaner and the etching unit in the loader.

10. (Original) The apparatus according to claim 6, wherein the substrate includes at least one of a gate electrode, a source electrode, a drain electrode, a pixel electrode, and a protective layer.

11. (Original) The apparatus according to claim 6, wherein the substrate includes at least one of a black matrix and a common electrode.

12. (Original) The apparatus according to claim 6, further comprising:

a tilt drain part flowing an etchant on the substrate;

a de-ionized rinse part eliminating the etchant on the substrate; and

a spin drier drying a de-ionized water.

13-18. (Canceled)